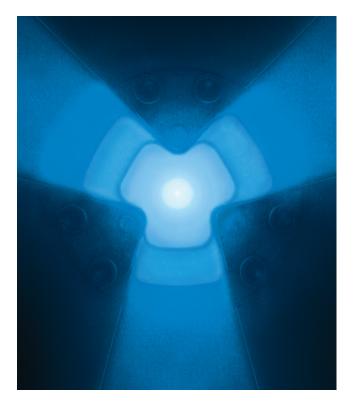
# EQ-10 EUV Light Source

## Electrodeless Z-Pinch<sup>™</sup> 10 Watt EUV Source

The EQ-10 is a compact, easy-to-use, reliable, and cost-effective EUV light source, based on Energetiq's proven Electrodeless Z-Pinch<sup>™</sup> technology using Xenon gas. The EQ-10 EUV source is uniquely suited for metrology and research applications. The EQ-10 has become the workhorse EUV source for the EUV community, through its proven reliability, ease of use, and low operating cost.

The Energetiq EQ-10 EUV Source's modular design makes it ready to be integrated in a process tool. The system includes the electrodeless Z-pinch source assembly, vacuum and gas subsystems, power delivery subsystem, and control electronics. The EQ-10 is capable of delivering up to 10 Watts of inband EUV into  $2\pi$  steradians and will run continuously at pulse repetition rates of up to 2 kHz.



Electrodeless Z-Pinch Source - View of visible light



# Features & Benefits

#### Performance

- 10W into  $2\pi$  using Xenon
- Up to 2 kHz pulse rate
- Small plasma size
- Low debris

### Low Cost of Ownership

- Low Xenon flow rate
- Minimized consumable cost
- Small footprint

### **Proven Reliability**

- Patented Electrodeless Z-Pinch technology
- CE-Mark and SEMI S2-0703 compliant

# **Applications**

- EUV Metrology
- EUV Resist Development
- Defect Inspection
- EUV Microscopy



## **Electrodeless Z-Pinch<sup>™</sup> Technology**

Z-pinch plasmas have been shown in the literature to be effective at producing EUV and SXR light. However, all the implementations to date have involved conducting high discharge currents into the plasma using electrodes. These electrodes, which are typically in contact with high temperature plasma, can melt and produce significant debris.

Energetiq's unique technology is also based on a Z-pinch plasma, but it avoids electrodes entirely by inductively coupling the current into the plasma. The plasma in the Energetiq source is magnetically confined away from the source walls, minimizing the heat load and reducing debris. Energetiq's Electrodeless Z-Pinch technology has excellent spatial stability, and stable repeatable power output.

## **Specifications**

<b>EUV Performance</b> • EUV Power Output • Pulse Repetition Rate • Source Operating Pressure • Xenon Flow Rate	10 Watts into 2π steradians (13.5 nm, ±1% bandwi 1200 to 2000 Hz 70 to 100 mTorr typical 5 to 15 sccm typical	dth)
Physical Specifications EQ-10RH		
<ul> <li>Instrument Rack</li> <li>Modulator</li> <li>Source</li> <li>Fore Pump Assembly</li> </ul>	<b>System Dimensions (H x W x D)</b> 1356 x 611 x 915 mm (53.4 x 24.1 x 36.0 in) 498 x 356 x 701 mm (19.6 x 14.0 x 27.6 in) 764 x 556 x 533 mm (30.1 x 21.9 x 21.0 in) 643 x 259 x 460 mm (30.1 x 21.9 x 21.0 in)	<b>Weight</b> 215.5 kg (475 lbs) 54.4 kg (120 lbs) 95.3 kg (210 lbs) 27.7 kg (61 lbs)
Utility Requirements <ul> <li>Electrical</li> <li>Cooling Water</li> <li>Clean Dry Air</li> <li>Xenon</li> </ul>	200–230V, 3Ø, 50/60 Hz, 30A 40-60 PSID (0.28–0.41 MPa), 1.5 GPM (5.7 lpm) min., 30°C max. inlet 75–90 PSIG (0.52–0.62 MPa) 15–40 PSIG (0.10–0.28 MPa), 20 sccm max. (10 sccm typ.)	
Compliance • EQ-10 Series	CE Mark, SEMI S2-0703	

#### Patent Numbers:

US 7,307,375 US 7,199,384 US 7,183,717 US 7,948,185 US 8,143,790 EP 2187711 Other patents applied for.

#### About Energetiq...

Energetiq Technology, Inc. is a developer and manufacturer of advanced short wavelength light products that enable nano-scale structures and products. The Energetiq team combines its deep understanding of the high power plasma physics needed for short wavelength light generation with its long experience in building rugged, industrial and scientific products. The result is that users can expect the highest levels of performance combined with the highest reliability.



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